

The documentation and process conversion measures necessary to comply with this revision shall be completed by 27 October 2016.

INCH-POUND

MIL-PRF-19500/684G
27 July 2016
SUPERSEDING
MIL-PRF-19500/684F
15 April 2016

PERFORMANCE SPECIFICATION SHEET

* TRANSISTOR, FIELD EFFECT, SILICON, N-CHANNEL, RADIATION HARDENED, ENCAPSULATED (SURFACE MOUNT AND CARRIER BOARD PACKAGES), TYPES 2N7472, 2N7473, AND 2N7474, JANTXVR AND JANSR

This specification is approved for use by all Departments and Agencies of the Department of Defense.

The requirements for acquiring the product described herein shall consist of this specification sheet and [MIL-PRF-19500](#).

1. SCOPE

1.1 Scope. This specification covers the performance requirements for N-channel, enhancement-mode, MOSFET, radiation hardened (total dose and single event effects (SEE)), power transistors. Two levels of product assurance (JANTXV and JANS) are provided for each encapsulated device, with avalanche energy maximum rating (E_{AS}) and maximum avalanche current (I_{AS}). Provisions for radiation hardness assurance (RHA) to two radiation levels ("R" and "F") are provided for JANTXV product assurance level. See 6.7 for JANHC and JANKC die versions.

* 1.2 Package outlines. The device package outlines are as follows: TO-276AC in accordance with [figure 1](#), TO-276AC with lead option (U2L) in accordance with [figure 2](#), SMD2 TO-276AC with carrier board option (U2S) in accordance with [figure 3](#) for all encapsulated device types.

* 1.3 Maximum ratings. $T_A = +25^\circ\text{C}$, unless otherwise specified.

Type (1)	P_T (2) $T_C = +25^\circ\text{C}$	P_T $T_A = +25^\circ\text{C}$	$R_{\theta JC}$ (3)	$R_{\theta J}$ Carrier	$R_{\theta J}$ Lid U2L (4)	V_{DS}	V_{DG}	V_{GS}	I_{D1} $T_C = +25^\circ\text{C}$ (5) (6)	I_{D2} $T_C = +100^\circ\text{C}$ (5) (6)	I_S	I_{DM} (7)	T_J and T_{STG}
	<u>W</u>	<u>W</u>	<u>$^\circ\text{C/W}$</u>	<u>$^\circ\text{C/W}$</u>	<u>$^\circ\text{C/W}$</u>	<u>V dc</u>	<u>V dc</u>	<u>V dc</u>	<u>A dc</u>	<u>A dc</u>	<u>A dc</u>	<u>A (pk)</u>	<u>$^\circ\text{C}$</u>
2N7472U2	250	2.5	0.5	1.5	10	130	130	± 20	75	57	75	300	-55
2N7473U2	250	2.5	0.5	1.5	10	200	200	± 20	53.5	34	53.5	214	to
2N7474U2	250	2.5	0.5	1.5	10	250	250	± 20	45	28	45	180	+150

* (1) Unless otherwise specified, electrical characteristics, ratings, and conditions for "U2L" and "U2S" suffix devices are identical to the corresponding "U2" suffix devices.

* (2) Derate linearly by 2.0 W/ $^\circ\text{C}$ for $T_C > +25^\circ\text{C}$, applies to U2 suffix devices only.

* (3) See [figure 4](#), thermal impedance curves, applies to U2 suffix devices only.

* (4) The Thermal resistance is applicable for mounting methods where a heatsink is attached to the lid for U2L suffix devices.

(5) The following formula derives the maximum theoretical I_D limit. I_D is limited by package and internal construction.

$$I_D = \sqrt{\frac{T_{JM} - T_C}{(R_{\theta JC}) \times (R_{DS(on)} \text{ at } T_{JM})}}$$

(6) See [figure 5](#), maximum drain current graph.

(7) $I_{DM} = 4 \times I_{D1}$ as calculated in note (5).

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AMSC N/A

FSC 5961



1.4 Primary electrical characteristics at $T_C = +25^\circ\text{C}$.

Type	Min $V_{(BR)DSS}$ $V_{GS} = 0$ $I_D = 1.0\text{mA}$ dc	$V_{GS(TH)1}$ $V_{DS} \geq V_{GS}$ $I_D = 1.0\text{mA}$ dc	Max I_{DSS1} $V_{GS} = 0$ $V_{DS} = 80\%$ of rated V_{DS}	Max $r_{DS(on)}$ (1) $V_{GS} = 12\text{V}$, $I_D = I_{D2}$		$R_{\theta JC}$ Max	E_{AS}
				$T_J = +25^\circ\text{C}$	$T_J = +150^\circ\text{C}$		
	<u>V dc</u>	<u>V dc</u> Min Max	<u>$\mu\text{A dc}$</u>	<u>Ω</u>	<u>Ω</u>	<u>$^\circ\text{C/W}$</u>	<u>mJ</u>
2N7472U2	130	2.5 4.5	10	0.0135	0.031	0.50	280
2N7473U2	200	2.5 4.5	10	0.038	0.087	0.50	380
2N7474U2	250	2.5 4.5	10	0.060	0.126	0.50	222

(1) Pulsed (see 4.5.1).

1.5 Part or Identifying Number (PIN). The PIN is in accordance with [MIL-PRF-19500](#), and as specified herein. See 6.4 for PIN construction example and 6.5 for a list of available PINs.

1.5.1 JAN certification mark and quality level for encapsulated devices. The quality level designators for encapsulated devices that are applicable for this specification sheet from the lowest to the highest level are as follows: "JANTXV" and "JANS".

1.5.2 Radiation hardness assurance (RHA) designator. The RHA levels that are applicable for this specification sheet from lowest to highest are as follows: "R" and "F".

1.5.3 Device type. The designation system for the device types of transistors covered by this specification sheet are as follows.

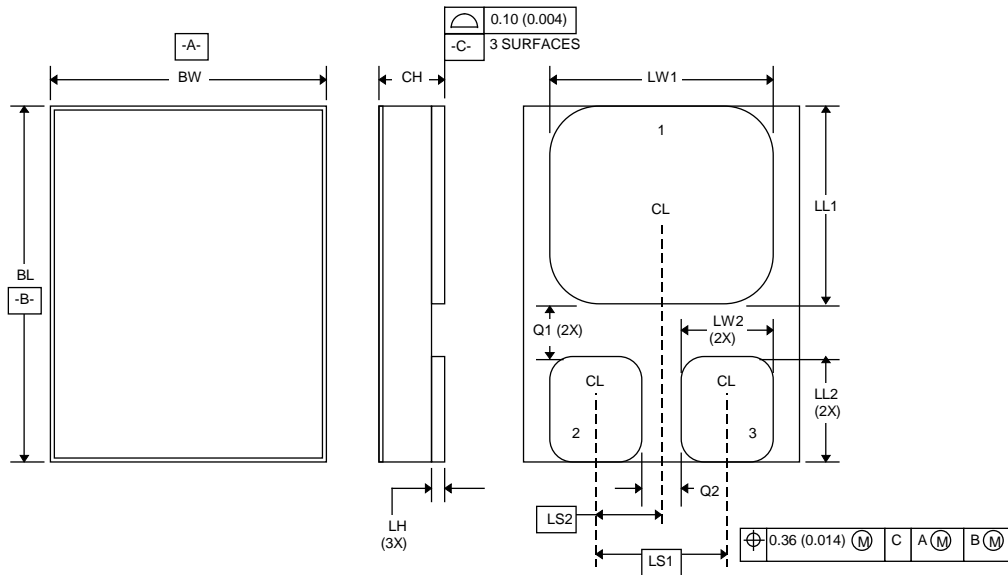
1.5.3.1 First number and first letter symbols. The transistors of this specification sheet use the first number and letter symbols "2N".

1.5.3.2 Second number symbols. The second number symbols for the transistors covered by this specification sheet are as follows: "7472", "7473", and "7374".

* 1.5.3.3 Suffix letters. The suffix letters "U2" are used on devices that are packaged in the SMD2 TO-276AC package of [figure 1](#). The suffix letters "U2L" are used on devices that are packaged in the SMD2 TO-276AC package and have additional flat leads added, see [figure 2](#). The suffix letters "U2S" are used on devices that are packaged in the SMD2 TO-276AC package mounted to a carrier board, see [figure 3](#).

1.5.4 Lead finish. The lead finishes applicable to this specification sheet are listed on [QPDSIS-19500](#).

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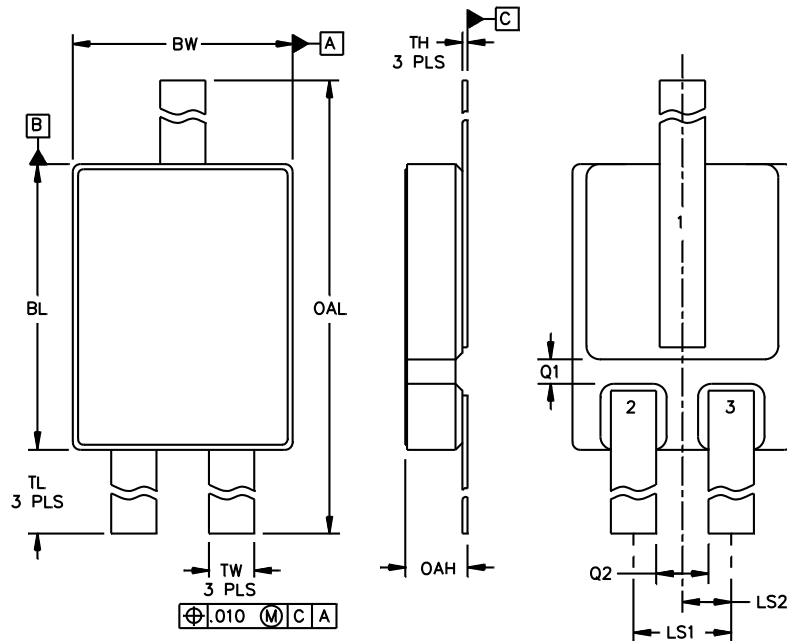


Symbol	Dimensions			
	Inches		Millimeters	
	Min	Max	Min	Max
BL	.685	.695	17.40	17.65
BW	.520	.530	13.21	13.46
CH		.142		3.60
LH	.010	.020	0.26	0.50
LW1	.435	.445	11.05	11.30
LW2	.135	.145	3.43	3.68
LL1	.470	.480	11.94	12.19
LL2	.152	.162	3.86	4.12
LS1	.240 BSC		6.10 BSC	
LS2	.120 BSC		3.05 BSC	
Q1	.035		0.89	
Q2	.050		1.27	
Term 1	Drain			
Term 2	Gate			
Term 3	Source			

NOTES:

1. Dimensions are in inches.
2. Millimeters are given for general information only.
3. In accordance with ASME Y14.5M, diameters are equivalent to ϕ x symbology.
4. Terminal 1 – Drain, Terminal 2 – Gate, Terminal 3 – Source.

FIGURE 1. Physical dimensions for surface mount U2 (TO-276AC).

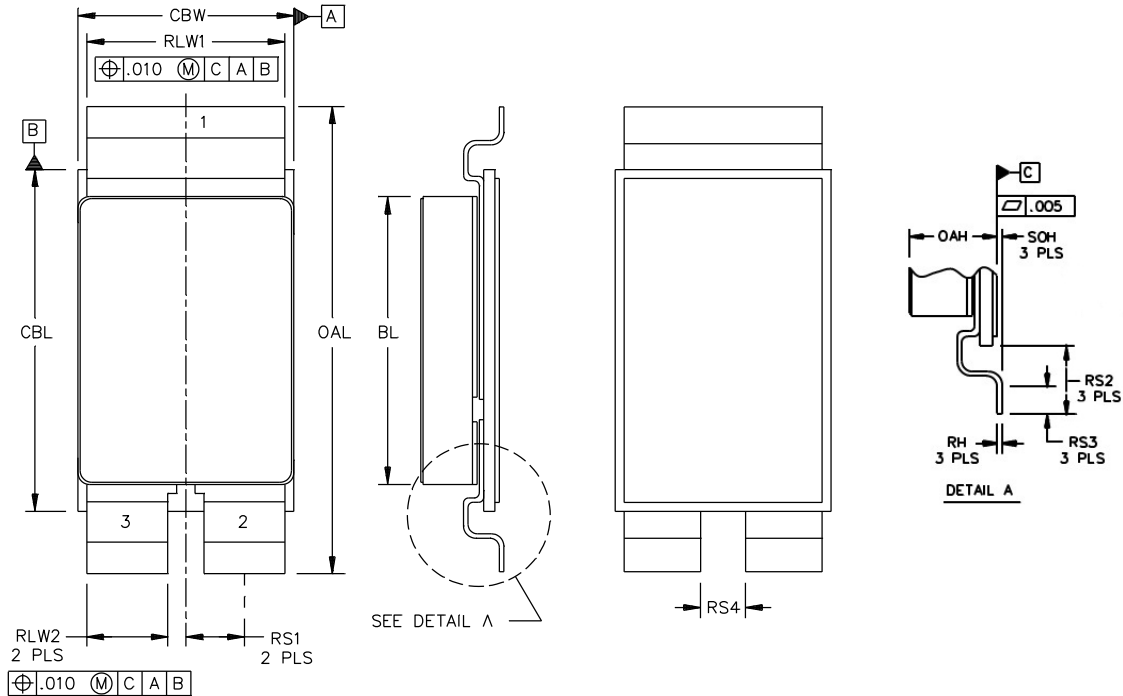


Symbol	Dimensions			
	Inches		Millimeters	
	Min	Max	Min	Max
BL	.685	.695	17.40	17.65
BW	.520	.530	13.21	13.46
LS1	.240 BSC		6.10 BSC	
LS2	.120 BSC		3.05 BSC	
Q1	.035		0.89	
Q2	.050		1.27	
TH	.005	.007	0.127	0.177
TL	.650	.675	16.52	17.14
TW	.095	.105	2.42	2.66
OAH		.150		3.81
OAL	1.985	2.045	50.42	51.94
TERM 1	Drain			
TERM 2	Gate			
TERM 3	Source			

NOTES:

1. Dimensions are in inches.
2. Millimeters are given for general information only.
3. The lid shall be electrically isolated from the drain, gate and source.
4. In accordance with ASME Y14.5M, diameters are equivalent to ϕ x symbology.

FIGURE 2. Physical dimensions, U2 with leaded option (U2L suffix).



Symbol	Dimensions			
	Inches		Millimeters	
	Min	Max	Min	Max
BL	.685	.695	17.40	17.65
CBL	.825	.840	20.96	21.34
CBW	.520	.535	13.21	13.59
OAH	.174	.204	4.42	5.18
OAL	1.109	1.144	28.17	29.06
RH	.009	.015	0.23	0.38
RLW1	.473	.497	12.01	12.62
RLW2	.178	.202	4.52	5.13
RS1	.1475 BSC		3.75 BSC	
RS2	.142	.152	3.61	3.86
RS3	.045	.055	1.14	1.40
RS4	.093		2.36	
SOA	.005	.015	0.13	0.38
TERM 1	Drain			
TERM 2	Gate			
TERM 3	Source			

NOTES:

1. Dimensions are in inches.
2. Millimeters are given for general information only.
3. The lid shall be electrically isolated from the drain, gate and source.
4. In accordance with ASME Y14.5M, diameters are equivalent to ϕ x suffix.

*

FIGURE 3. Physical dimensions, U2 with carrier board option (U2S suffix).

2. APPLICABLE DOCUMENTS

2.1 General. The documents listed in this section are specified in sections 3 and 4 of this specification. This section does not include documents cited in other sections of this specification or recommended for additional information or as examples. While every effort has been made to ensure the completeness of this list, document users are cautioned that they must meet all specified requirements of documents cited in sections 3 and 4 of this specification, whether or not they are listed.

2.2 Government documents.

2.2.1 Specifications, standards, and handbooks. The following specifications, standards, and handbooks form a part of this document to the extent specified herein. Unless otherwise specified, the issues of these documents are those cited in the solicitation or contract.

DEPARTMENT OF DEFENSE SPECIFICATIONS

[MIL-PRF-19500](#) - Semiconductor Devices, General Specification for.

DEPARTMENT OF DEFENSE STANDARDS

[MIL-STD-750](#) - Test Methods for Semiconductor Devices.

(Copies of these documents are available online at <http://quicksearch.dla.mil/>.)

2.3 Order of precedence. Unless otherwise noted herein or in the contract, in the event of a conflict between the text of this document and the references cited herein, the text of this document takes precedence. Nothing in this document, however, supersedes applicable laws and regulations unless a specific exemption has been obtained.

3. REQUIREMENTS

3.1 General. The individual item requirements shall be as specified in [MIL-PRF-19500](#) and as modified herein.

3.2 Qualification. Devices furnished under this specification shall be products that are manufactured by a manufacturer authorized by the qualifying activity for listing on the applicable qualified manufacturer's list (QML) before contract award (see [4.2](#) and [6.3](#)).

3.3 Abbreviations, symbols, and definitions. Abbreviations, symbols, and definitions used herein shall be as specified in [MIL-PRF-19500](#).

* 3.4 Interface and physical dimensions. The interface and physical dimensions shall be as specified in [MIL-PRF-19500](#) and on [figures 1](#) (U2, TO-276AC), [2](#) (U2L, surface mount TO-276AC with additional flat leads added) and [3](#) (U2S, surface mount TO-276AC with additional flat leads added and mounted to a carrier board) herein. Methods used for the electrical isolation of the terminals shall employ materials that contain a minimum of 90 percent Al₂O₃ (ceramic).

3.4.1 Lead finish. Unless otherwise specified, lead finish shall be solderable in accordance with [MIL-PRF-19500](#), [MIL-STD-750](#), and herein. Where a choice of lead finish is desired, it shall be specified in the acquisition document (see [6.2](#)).

3.4.2 Multiple chip construction. Multiple chip construction is not permitted to meet the requirements of this specification.

* 3.4.3 Lead attach or Carrier package. Alternations to the device shall be performed on devices that have passed all screening and QCI required per [MIL-PRF-19500](#) and listed herein. When leads or carrier attach is added to the U2 package, as a minimum, the vendor shall perform the tests specified in [4.3.4](#) herein.

* 3.5 Marking. Marking shall be in accordance with [MIL-PRF-19500](#). At the option of the manufacturer, marking may be omitted from the body, but shall be retained on the initial container. Devices that have been altered with lead or carrier attached per the specification herein shall have the altered part number on the device or on the device packaging.

3.6 Electrostatic discharge protection. The devices covered by this specification require electrostatic discharge protection.

3.6.1 Handling. MOS devices must be handled with certain precautions to avoid damage due to the accumulation of static charge. However, the following handling practices are recommended (see [3.6](#)).

- a. Devices should be handled on benches with conductive handling devices.
- b. Ground test equipment, tools, and personnel handling devices.
- c. Do not handle devices by the leads.
- d. Store devices in conductive foam or carriers.
- e. Avoid use of plastic, rubber, or silk in MOS areas.
- f. Maintain relative humidity above 50 percent if practical.
- g. Care should be exercised during test and troubleshooting to apply not more than maximum rated voltage to any lead.
- h. Gate must be terminated to source, $R \leq$ or 100 k Ω , whenever bias voltage is applied drain to source.

3.7 Electrical performance characteristics. Unless otherwise specified herein, the electrical performance characteristics are as specified in [1.3](#), [1.4](#), and [table I](#).

3.8 Electrical test requirements. The electrical test requirements shall be as specified in [table I](#).

3.9 Workmanship. Semiconductor devices shall be processed in such a manner as to be uniform in quality and shall be free from other defects that will affect life, serviceability, or appearance.

4. VERIFICATION

4.1 Classification of inspections. The inspection requirements specified herein are classified as follows:

- a. Qualification inspection (see [4.2](#)).
- b. Screening (see [4.3](#)).
- c. Conformance inspection (see [4.4](#) and tables I and II).

4.2 Qualification inspection. Qualification inspection shall be in accordance with [MIL-PRF-19500](#) and as specified herein.

* 4.2.1 Group E qualification. Group E inspection shall be performed for qualification or re-qualification only. In case qualification was awarded to a prior revision of the specification sheet that did not request the performance of [table III](#) tests, the tests specified in [table III](#) (and [table IV](#) as applicable) herein that were not performed in the prior revision shall be performed on the first inspection lot of this revision to maintain qualification.

4.2.1.1 Single event effects (SEE). SEE shall be performed at initial qualification and after process or design changes which may affect radiation hardness (see [table III](#) and [table V](#)). Upon qualification, manufacturers shall provide the verification test conditions from section 5 of method 1080 of [MIL-STD-750](#) that were used to qualify the device for inclusion into section 6 of the slash sheet. End-point measurements shall be in accordance with [table II](#). SEE characterization data shall be made available upon request of the qualifying or acquiring activity.

4.3 Screening (JANS and JANTXV). Screening shall be in accordance with table E-IV of MIL-PRF-19500 and as specified herein. The following measurements shall be made in accordance with table I herein. Devices that exceed the limits of table I herein shall not be acceptable.

Screen (see table E-IV of MIL-PRF-19500) (1) (2)	Measurement	
	JANS	JANTXV
(3)	Gate stress test (see 4.3.1)	Gate stress test (see 4.3.1)
(3)	Method 3470 of MIL-STD-750, E _{AS} (see 4.3.2)	Method 3470 of MIL-STD-750, E _{AS} (see 4.3.2)
(3) 3c	Method 3161 of MIL-STD-750, thermal impedance, (see 4.3.3)	Method 3161 of MIL-STD-750, thermal impedance, (see 4.3.3)
9	Subgroup 2 of table I herein I _{DSS1} , I _{GSSF1} , I _{GSSR1} as minimum	Not applicable
10	Method 1042 of MIL-STD-750, test condition B	Method 1042 of MIL-STD-750, test condition B
11	I _{GSSF1} , I _{GSSR1} , I _{DSS1} , r _{DS(ON)1} , V _{GS(TH)1} Subgroup 2 of table I herein. $\Delta I_{GSSF1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{GSSR1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{DSS1} = \pm 10 \text{ } \mu\text{A dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$	I _{GSSF1} , I _{GSSR1} , I _{DSS1} , r _{DS(ON)1} , V _{GS(TH)1} Subgroup 2 of table I herein.
12	Method 1042 of MIL-STD-750, test condition A	Method 1042 of MIL-STD-750, test condition A
13	Subgroups 2 and 3 of table I herein $\Delta I_{GSSF1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{GSSR1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{DSS1} = \pm 10 \text{ } \mu\text{A dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta r_{DS(ON)1} = \pm 20 \text{ percent of initial value.}$ $\Delta V_{GS(TH)1} = \pm 20 \text{ percent of initial value.}$	Subgroup 2 of table I herein $\Delta I_{GSSF1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{GSSR1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{DSS1} = \pm 10 \text{ } \mu\text{A dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta r_{DS(ON)1} = \pm 20 \text{ percent of initial value.}$ $\Delta V_{GS(TH)1} = \pm 20 \text{ percent of initial value.}$

- (1) At the end of the test program, I_{GSSF1}, I_{GSSR1}, and I_{DSS1} are measured.
- (2) An out-of-family program to characterize I_{GSSF1}, I_{GSSR1}, I_{DSS1}, V_{GS(th)1}, and r_{DS(ON)1} shall be invoked.
- (3) Shall be performed anytime after temperature cycling, screen 3a; JANTXV level does not need to be repeated in screening requirements.

4.3.1 Gate stress test. Apply $V_{GS} = 24$ V minimum for $t = 250$ μ s minimum.

4.3.2 Single pulse avalanche energy (E_{AS}).

- a. Peak current (I_{AS})..... I_{D1} .
- b. Peak gate voltage (V_{GS}).....12 V dc.
- c. Gate to source resistor (R_{GS})..... $25 \leq R_{GS} \leq 200 \Omega$.
- d. Initial case temperature+25°C, +10°C, -5°C.
- e. Inductance: $\left[\frac{2E_{AS}}{(I_{D1})^2} \right] \left[\frac{V_{BR} - V_{DD}}{V_{BR}} \right]$ mH minimum.
- f. Number of pulses to be applied1 pulse minimum.
- g. Supply voltage (V_{DD}).....50 V dc.

4.3.3 Thermal impedance. The thermal impedance measurements shall be performed in accordance with method 3161 of MIL-STD-750 using the guidelines in that method for determining I_M , I_H , t_H , t_{SW} , (and V_H where appropriate). See table III, group E, subgroup 4 herein.

* 4.3.4 Lead or carrier attach screening (All quality levels). All surface mount devices with added leads or carrier boards shall be screened as specified herein.

Screen	MIL-STD-750 Method	Conditions
1. Hermetic Seal 1/ a. Fine Leak b. Gross Leak	1071	
2. Thermal Response (see 4.3.3) A2 dc Electrical 2/ 3/	3161	Read and Record.
3. X-Radiography	2076	The solder material coverage at the package lead pad/SMD carrier sub interfaces shall be 85% minimum
4. External Visual Examination	2071	Cracks or separation of materials shall not be evident on any device after the SMD lead attach assembly operation. Pad and Isolation areas shall be free from foreign matter and extraneous solder. Solder fillet coverage at the lead/package lead pad interfaces, along all visible sides, minimum of 75% solder fillet coverage.
5a. Physical dimensions	2066	6 piece sample, each device shall meet the requirements specified in figures 2 and 3.
5b. Terminal Strength	2036	3 piece sample.

1/ Evaluation of surface sorption in accordance with method 1071 shall be performed.

2/ Only DC electrical test specified herein.

3/ When lead carrier bend is requested, the electrical test is performed prior to the bend process.

4.4 Conformance inspection. Conformance inspection shall be in accordance with [MIL-PRF-19500](#) and as specified herein.

4.4.1 Group A inspection. Group A inspection shall be conducted in accordance with table E-V of [MIL-PRF-19500](#) and [table I](#) herein.

4.4.2 Group B inspection. Group B inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VIA (JANS) and table E-VIB (JANTXV) of [MIL-PRF-19500](#), and as follows.

4.4.2.1 Quality level JANS, table E-VIA of [MIL-PRF-19500](#).

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
B3	1051	Test condition G, 100 cycles.
B3	2077	SEM.
B4	1042	Intermittent operation life, condition D. No heat sink or forced-air cooling on the device shall be permitted during the on cycle. $t_{on} = 30$ seconds minimum.
B5	1042	Accelerated steady-state gate bias, condition B, $V_{GS} = \text{rated}$; $T_A = +175^{\circ}\text{C}$, $t = 24$ hours minimum; or $T_A = +150^{\circ}\text{C}$, $t = 48$ hours minimum.
B5	1042	Accelerated steady-state reverse bias, condition A, $V_{DS} = \text{rated}$; $T_A = +175^{\circ}\text{C}$, $t = 120$ hours minimum; or $T_A = +150^{\circ}\text{C}$, $t = 240$ hours minimum.

4.4.2.2 Quality levels JAN, JANTX and JANTXV, table E-VIB of [MIL-PRF-19500](#).

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
B2	1051	Test condition G, 25 cycles.
B3	1042	Intermittent operation life, condition D. No heat sink or forced-air cooling on the device shall be permitted during the on cycle. $t_{on} = 30$ seconds minimum.

* 4.4.3 Group C inspection. Group C inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VII of [MIL-PRF-19500](#) and as follows.

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
C2	2036	Terminal strength is not applicable.
* C5	3161	Thermal resistance, see 4.3.3 .
C6	1042	Intermittent operation life, condition D. No heat sink or forced-air cooling on the device shall be permitted during the on cycle. $t_{on} = 30$ seconds minimum.

4.4.4 Group D inspection. Group D inspection shall be conducted in accordance with table E-VIII of [MIL-PRF-19500](#) and [table II](#) herein.

* 4.4.5 Group E inspection. Group E inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-IX of [MIL-PRF-19500](#) and as specified in [table III](#) (and [table IV](#) as applicable) herein.

4.5 Methods of inspection. Methods of inspection shall be as specified in the appropriate tables and as follows.

4.5.1 Pulse measurements. Conditions for pulse measurement shall be as specified in section 4 of [MIL-STD-750](#).

*

TABLE I. Group A inspection.

Inspection 1/	MIL-STD-750		Symbol	Limits		Unit
	Method	Condition		Min	Max	
<u>Subgroup 1</u>						
Visual and mechanical inspection	2071					
<u>Subgroup 2</u>						
Thermal impedance 2/	3161	See 4.3.3	$Z_{\theta JC}$			°C/W
Breakdown voltage drain to source 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3407	$V_{GS} = 0$, $I_D = 1$ mA dc, bias condition C	$V_{(BR)DSS}$	130 200 250		V dc V dc V dc
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}$, $I_D = 1$ mA dc	$V_{GS(TH)1}$	2.5	4.5	V dc
Gate current	3411	$V_{GS} = +20$ V dc, bias condition C, $V_{DS} = 0$	I_{GSSF1}		+100	nA dc
Gate current	3411	$V_{GS} = -20$ V dc, bias condition C, $V_{DS} = 0$	I_{GSSR1}		-100	nA dc
Drain current	3413	$V_{GS} = 0$, bias condition C, $V_{DS} = 80$ percent of rated V_{DS} ,	I_{DSS1}		10	μA dc
Static drain to source on-state resistance 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3421	$V_{GS} = 12$ V dc, condition A, pulsed (see 4.5.1), $I_D = I_{D2}$	$r_{DS(ON)1}$		0.0135 0.038 0.060	Ω Ω Ω
Forward voltage 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	4011	$V_{GS} = 0$, condition A, pulsed (see 4.5.1), $I_D = I_{D1}$	V_{SD}		1.2 1.2 1.2	V dc V dc V dc
<u>Subgroup 3</u>						
High temperature operation		$T_C = T_J = +125^\circ\text{C}$				
Gate current	3411	$V_{GS} = \pm 20$ V dc, bias condition C, $V_{DS} = 0$	I_{GSS2}		±200	nA dc
Drain current	3413	$V_{GS} = 0$, bias condition C, $V_{DS} = 80$ percent of rated V_{DS}	I_{DSS2}		25	μA dc

See footnotes at end of table.

*

TABLE I. Group A inspection - Continued.

Inspection 1/	MIL-STD-750		Symbol	Limits		Unit
	Method	Condition		Min	Max	
<u>Subgroup 3</u> - continued						
Static drain to source on-state resistance 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3421	$V_{GS} = 12 \text{ V dc}$, condition A, pulsed (see 4.5.1), $I_D = I_{D2}$	$r_{DS(ON)3}$		0.028 0.080 0.126	Ω Ω Ω
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}$, $I_D = 1 \text{ mA dc}$	$V_{GS(TH)2}$	1.5		V dc
Low temperature operation		$T_C = T_J = -55^{\circ}\text{C}$				
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS(TH)3}$, $I_D = 1 \text{ mA dc}$	$V_{GS(TH)3}$		5.5	V dc
<u>Subgroup 4</u>						
Forward transconductance 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3475	$I_D = I_{D2}$, $V_{DD} = 15 \text{ V dc}$, (see 4.5.1)	g_{FS}	39 35 27		S S S
Switching time test	3472	$I_D = I_{D1}$, $V_{GS} = 12 \text{ V dc}$ $R_G = 2.35 \Omega$, $V_{DD} = 50$ percent of rated V_{DS}				
Turn-on delay time 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S			$t_{D(on)}$		35 35 35	ns ns ns
Rise time 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S			t_r		125 125 125	ns ns ns
Turn-off delay time 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S			$t_{D(off)}$		80 80 80	ns ns ns
Fall time 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S			t_f		50 50 65	ns ns ns

See footnotes at end of table.

*

TABLE I. Group A inspection - Continued.

Inspection 1/	MIL-STD-750		Symbol	Limits		Unit		
	Method	Condition		Min	Max			
<u>Subgroup 5</u>	3474	See figure 6, 7, and 8 $t_p = 10$ ms min. $V_{DS} = 80$ percent of max. rated V_{DS}						
Safe operating area test (high voltage)								
Electrical measurements		See table I, subgroup 2						
<u>Subgroup 6</u>	3471	Condition B $I_D = I_{D1}$	$Q_{G(ON)}$					
Not applicable								
<u>Subgroup 7</u>								
Gate charge								
On-state gate charge 2N7472U2, U2L, U2S							160	nC
2N7473U2, U2L, U2S							155	nC
2N7474U2, U2L, U2S					165	nC		
Gate to source charge 2N7472U2, U2L, U2S					55	nC		
2N7473U2, U2L, U2S					45	nC		
2N7474U2, U2L, U2S					45	nC		
Gate to drain charge 2N7472U2, U2L, U2S					75	nC		
2N7473U2, U2L, U2S					75	nC		
2N7474U2, U2L, U2S					75	nC		
Reverse recovery time	3473	$di/dt = -100$ A/ μ s, $V_{DD} \leq 50$ V $I_D = I_{D1}$	t_{rr}					
2N7472U2, U2L, U2S				300	ns			
2N7473U2, U2L, U2S				450	ns			
2N7474U2, U2L, U2S				560	ns			

1/ For sampling plan, see MIL-PRF-19500.

2/ This test required for the following end-point measurements only:

Group B, subgroups 3 and 4 (JANS).

Group B, subgroups 2 and 3 (JANTXV).

Group C, subgroup 2 and 6.

Group E, subgroup 1.

*

TABLE II. Group D inspection.

Inspection 1/ 2/ 3/	MIL-STD-750		Symbol	Pre-irradiation limits		Post-irradiation limits		Unit
	Method	Conditions		R		R		
				Min	Max	Min	Max	
<u>Subgroup 1</u>								
Not applicable								
<u>Subgroup 2</u>		T _C = + 25°C						
Steady-state total dose irradiation (V _{GS} bias) 4/	1019	V _{GS} = 12 V; V _{DS} = 0						
Steady-state total dose irradiation (V _{DS} bias) 4/	1019	V _{GS} = 0; V _{DS} = 80 percent of rated V _{DS} (pre-irradiation)						
End-point electricals:								
Breakdown voltage, drain to source 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3407	V _{GS} = 0; I _D = 1 mA; bias condition C	V _{(BR)DSS}	130 200 250		130 200 250		V dc V dc V dc
Gate to source voltage (threshold) 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3403	V _{DS} ≥ V _{GS} I _D = 1 mA	V _{GS(th)1}	2.5 2.5 2.5	4.5 4.5 4.5	2.0 2.0 2.0	4.5 4.5 4.5	V dc V dc V dc
Gate current	3411	V _{GS} = +20 V, V _{DS} = 0, bias condition C	I _{GSSF1}		100		100	nA dc
Gate current	3411	V _{GS} = -20 V, V _{DS} = 0, bias condition C	I _{GSSR1}		-100		-100	nA dc
Drain current	3413	V _{GS} = 0, V _{DS} = 80 percent of rated V _{DS} (pre-irradiation) bias condition C	I _{DSS}		10		10	μA dc
Static drain to source on-state voltage 2N7472U2, U2L, U2S 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S	3405	V _{GS} = 12 V; condition A, pulsed (see 4.5.1), I _{D1} = I _{D2}	V _{DS(on)}		0.798 1.326 1.708		0.798 1.326 1.708	V dc V dc V dc
Forward voltage source drain diode	4011	V _{GS} = 0; I _D = I _{D1} bias condition A	V _{SD}		1.2		1.2	V dc

1/ For sampling plan see MIL-PRF-19500.

2/ Group D qualification may be performed prior to lot formation. Wafers qualified to these group D QCI requirements may be used for any other specification sheets utilizing the same die design.

3/ At the manufacturer's option, group D samples need not be subjected to the screening tests, and may be assembled in its qualified package or in any qualified package that the manufacturer has data to correlate the performance to the designated package.

4/ Separate samples shall be pulled for each bias.

* TABLE III. Group E inspection (all quality levels) for qualification or re-qualification only.

Inspection	MIL-STD-750		Sample plan
	Method	Conditions	
<u>Subgroup 1</u>			45 devices c = 0
Temperature cycling	1051	Condition G, 500 cycles	
Hermetic seal	1071	As applicable.	
Fine leak			
Gross leak			
Electrical measurements		See table I , subgroup 2	
<u>Subgroup 2 1/</u>			45 devices c = 0
Steady-state gate bias	1042	Condition B, 1,000 hours	
Electrical measurements		See table I , subgroup 2	
Steady-state reverse bias	1042	Condition A, 1,000 hours	
Electrical measurements		See table I , subgroup 2	
<u>Subgroup 4</u>			Sample size N/A
Thermal impedance curves		See MIL-PRF-19500 .	
<u>Subgroup 5</u>			3 devices c = 0
Barometric pressure	1001	Test condition C, $V_{DS} = 250 \text{ V}$; $I_{ISO} < 0.25 \text{ mA}$.	
2N7474U2, U2L, U2S only			
<u>Subgroup 10</u>			22 devices c = 0
Commutating diode for safe operating area test procedure for measuring dv/dt during reverse recovery of power MOSFET transistors or insulated gate bipolar transistors	3476	Test conditions shall be derived by the manufacturer.	
<u>Subgroup 11</u>			3 devices
SEE <u>2/ 3/</u>	1080	See MIL-STD-750 method 1080 and 6.2 .	

1/ A separate sample for each test shall be pulled.

2/ Group E qualification of SEE effect testing may be performed prior to lot formation. Qualification may be extended to other specification sheets utilizing the same structurally identical die design.

* 3/ Device qualification to a higher level linear energy transfer (LET) is sufficient to qualify all lower level LETs.

*

TABLE IV. Lead alternation Qualification inspection requirements.

Inspections <u>1/</u>	MIL-STD-750		Sample size
	Method	Conditions	
<u>Subgroup 1</u>			6 devices, c = 0
Temperature cycle	1051	100 Temp cycles, test condition G or maximum storage temperature.	
Hermetic seal	1071		
Fine leak			
Gross leak			
A2 dc electrical		Read and record.	
Thermal response	3161		
External visual examination	2071	Cracks or separation of materials shall not be evident on test samples.	
<u>Subgroup 2</u>			6 devices, c = 0
Intermittent operating life	1042	Condition D; 6,000 cycles.	
A2 dc electrical		Read and record.	
Thermal response	3161		
External visual examination	2071	Cracks or separation of materials shall not be evident on test samples.	
<u>Subgroup 3</u>			6 devices, c = 0
Terminal strength	2036	Tension; Condition A 10lbs for 10 seconds Fatigue; Condition E 3 arcs of 90 +/-5 degrees each 8.0 oz.	
A2 dc electrical		Read and record.	
External visual examination	2071	Cracks or separation of materials shall not be evident on test samples.	

1/ Qualification samples performed on non-formed leaded devices.

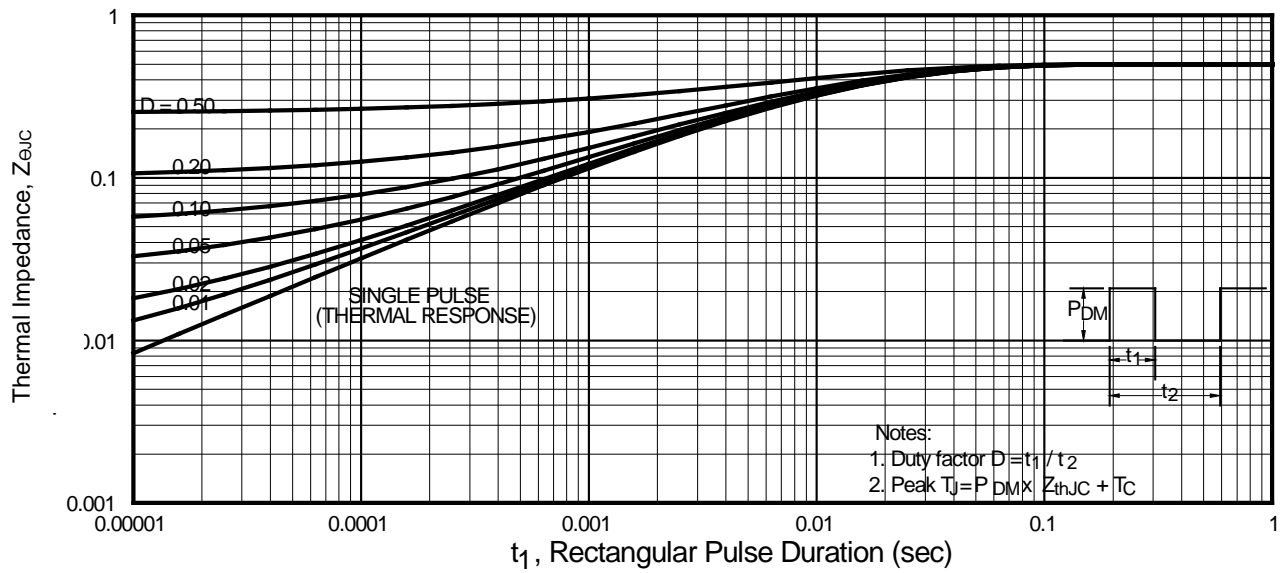
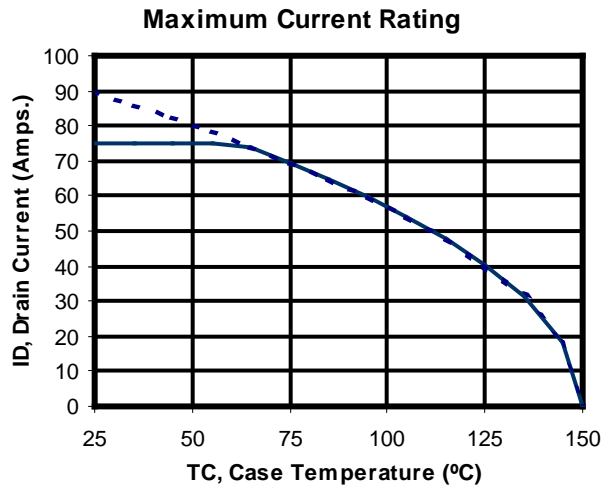
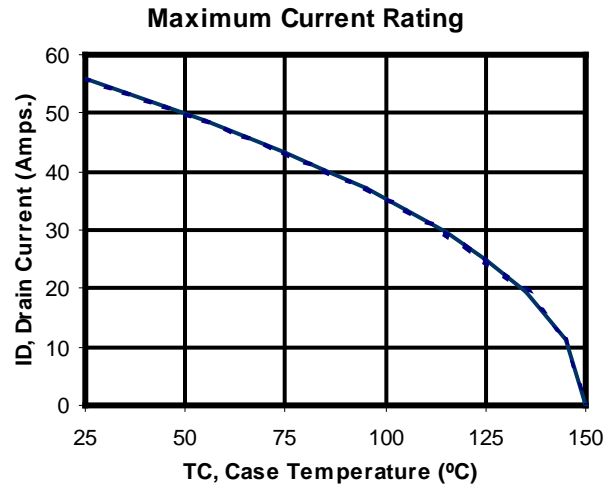


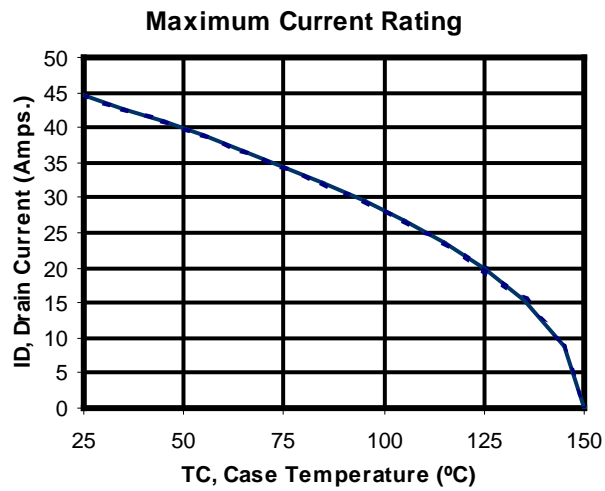
FIGURE 4. Thermal impedance curve.



2N7472U2, U2L, U2S



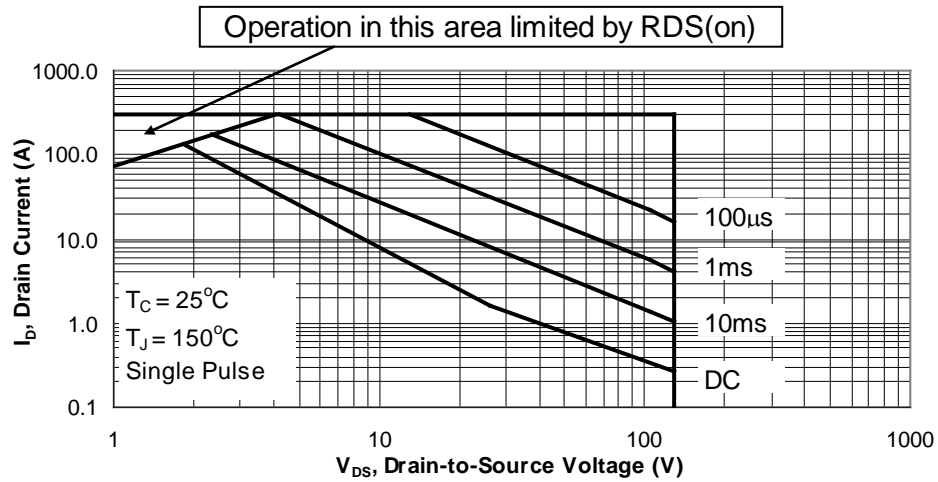
2N7473U2, U2L, U2S



2N7474U2, U2L, U2S

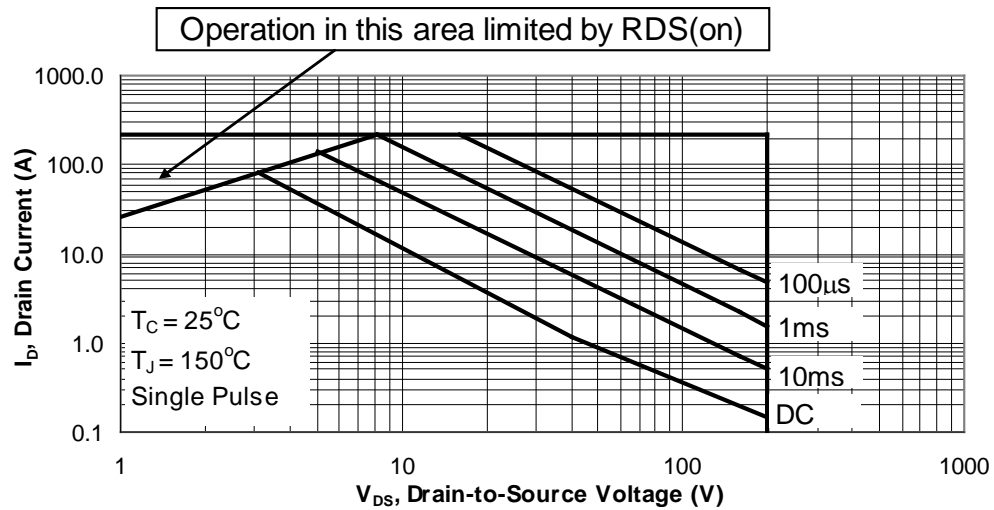
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FIGURE 5. Maximum drain current versus case temperature graphs.



2N7472U2, U2L, U2S

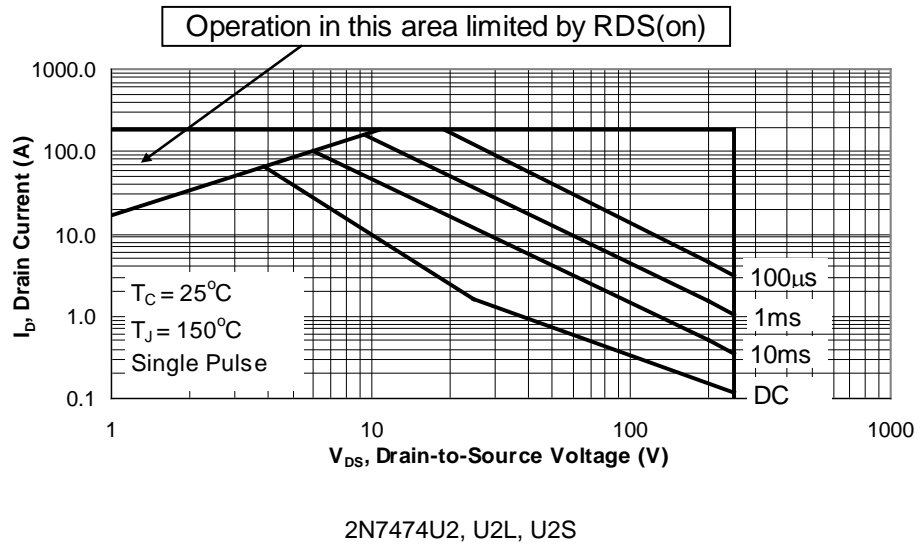
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FIGURE 6. Safe operating area graph.

2N7473U2, U2L, U2S

*

FIGURE 7. Safe operating area graph.



*

FIGURE 8. Safe operating area graph.

5. PACKAGING

5.1 Packaging. For acquisition purposes, the packaging requirements shall be as specified in the contract or order (see 6.2). When packaging of materiel is to be performed by DoD or in-house contractor personnel, these personnel need to contact the responsible packaging activity to ascertain packaging requirements. Packaging requirements are maintained by the Inventory Control Point's packaging activities within the Military Service or Defense Agency, or within the Military Service's system commands. Packaging data retrieval is available from the managing Military Department's or Defense Agency's automated packaging files, CD-ROM products, or by contacting the responsible packaging activity.

6. NOTES

(This section contains information of a general or explanatory nature that may be helpful, but is not mandatory. The notes specified in MIL-PRF-19500 are applicable to this specification.)

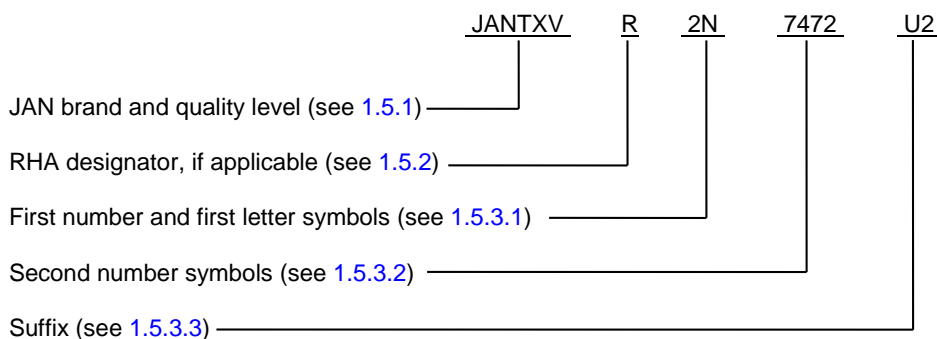
6.1 Intended use. Semiconductors conforming to this specification are intended for original equipment design applications and logistic support of existing equipment.

6.2 Acquisition requirements. Acquisition documents should specify the following:

- a. Title, number, and date of this specification.
- b. Packaging requirements (see 5.1).
- c. Lead finish (see 3.4.1).
- d. The complete PIN, see 1.5 and 6.5.
- e. For acquisition of RHA designated devices, table II, subgroup 1 testing of group D herein is optional. If subgroup 1 is desired, it should be specified in the contract or order.
- f. If SEE testing data is desired, it should be specified in the contract or order.
- g. If specific SEE characterization conditions are desired (see section 6.8 and table V), manufacturer's cage code should be specified in the contract or order.

6.3 Qualification. With respect to products requiring qualification, awards will be made only for products which are, at the time of award of contract, qualified for inclusion in Qualified Manufacturers List (QML 19500) whether or not such products have actually been so listed by that date. The attention of the contractors is called to these requirements, and manufacturers are urged to arrange to have the products that they propose to offer to the Federal Government tested for qualification in order that they may be eligible to be awarded contracts or orders for the products covered by this specification. Information pertaining to qualification of products may be obtained from DLA Land and Maritime, ATTN: VQE, P.O. Box 3990, Columbus, OH 43218-3990 or e-mail vqe.chief@dla.mil. An online listing of products qualified to this specification may be found in the Qualified Products Database (QPD) at <https://assist.dla.mil>.

6.4 PIN construction example. The PINs for encapsulated devices are construction using the following form.



* 6.5 List of PINs. The following is a list of possible PINs available on this specification sheet.

PINs for devices of the "TXV" quality level	PINs for devices of the "TXV" quality level with RHA (1)	PINs for devices of the "S" quality level	PINs for devices of the "S" quality level with RHA (1)
JANTXV2N7472U2	JANTXV#2N7472U2	JANS2N7472U2	JANS#2N7472U2
JANTXV2N7472U2L	JANTXV#2N7472U2L	JANS2N7472U2L	JANS#2N7472U2L
JANTXV2N7472U2S	JANTXV#2N7472U2S	JANS2N7472U2S	JANS#2N7472U2S
JANTXV2N7473U2	JANTXV#2N7473U2	JANS2N7473U2	JANS#2N7473U2
JANTXV2N7473U2L	JANTXV#2N7473U2L	JANS2N7473U2L	JANS#2N7473U2L
JANTXV2N7473U2S	JANTXV#2N7473U2S	JANS2N7473U2S	JANS#2N7473U2S
JANTXV2N7474U2	JANTXV#2N7474U2	JANS2N7474U2	JANS#2N7474U2
JANTXV2N7474U2L	JANTXV#2N7474U2L	JANS2N7474U2L	JANS#2N7474U2L
JANTXV2N7474U2S	JANTXV#2N7474U2S	JANS2N7474U2S	JANS#2N7474U2S

(1) The number sign (#) represents one of two RHA designators available on this specification sheet ("R" or "F").

6.6 Cross-reference list. The following table shows the generic P/N and its associated military P/N (without JAN and RHA prefix).

Generic P/N	Military P/N
IRHNA57163SE	2N7472U2
IRHNA57260SE	2N7473U2
IRHNA57264SE	2N7474U2

* 6.7 JANHC and JANKC die versions. The JANHC and JANKC die versions of these devices are covered under specification sheet [MIL-PRF-19500/741](https://assist.dla.mil).

6.8 Application data.

6.8.1 Manufacturer specific irradiation data. Each manufacturer qualified to this slash sheet has characterized its devices to the requirements of [MIL-STD-750](#) method 1080 and as specified herein. Since each manufacturer's characterization conditions can be different and can vary by the version of method 1080 qualified to, the [MIL-STD-750](#) method 1080 revision version date and conditions used by each manufacturer for characterization have been listed here (see [table V](#)) for information only. SEE conditions and figures listed in section 6 are current as of the date of this specification sheet, please contact the manufacturer for the most recent conditions.

*

TABLE V. Manufacturers characterization conditions.

Manufactures cage	Inspection	MIL-STD-750		Sample plan
		Method	Conditions	
69210 (Applicable to devices with a date code of 21 August 2012 and older)	SEE 1/	1080	See MIL-STD-750E method 1080.0 dated 20 November 2006. See figure 9	3 devices
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I, subgroup 2	
	SEE irradiation:		Fluence = $3E5 \pm 20$ percent ions/cm ² Flux = $2E3$ to $2E4$ ions/cm ² /sec, temperature = $25^\circ \pm 5^\circ \text{C}$	
	2N7472U2, U2L, U2S		Surface LET = 38 MeV-cm ² /mg $\pm 5\%$, range = 38 μm $\pm 7.5\%$, energy = 300 MeV $\pm 7.5\%$ In-situ bias conditions: $V_{DS} = 130 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (typical 3.75 MeV/nucleon at Texas A & M Cyclotron)	
	2N7473U2, U2L, U2S		In-situ bias conditions: $V_{DS} = 200 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (nominal 3.86 MeV/nucleon at Brookhaven National Lab Accelerator)	
	2N7474U2, U2L, U2S		In-situ bias conditions: $V_{DS} = 250 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (nominal 3.86 MeV/nucleon at Brookhaven National Lab Accelerator)	
	2N7472U2, U2L, U2S		Surface LET = 61 MeV-cm ² /mg $\pm 5\%$, range = 31 μm $\pm 10\%$, energy = 330 MeV $\pm 7.5\%$ In-situ bias conditions: $V_{DS} = 130 \text{ V}$ and $V_{GS} = -10 \text{ V}$ $V_{DS} = 100 \text{ V}$ and $V_{GS} = -15 \text{ V}$ $V_{DS} = 50 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (typical 2.70 MeV/nucleon at Texas A & M Cyclotron)	
	2N7473U2, U2L, U2S		In-situ bias conditions: $V_{DS} = 200 \text{ V}$ and $V_{GS} = -10 \text{ V}$ $V_{DS} = 185 \text{ V}$ and $V_{GS} = -15 \text{ V}$ $V_{DS} = 120 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (nominal 2.92 MeV/nucleon at Brookhaven National Lab Accelerator)	
	2N7474U2, U2L, U2S		In-situ bias conditions: $V_{DS} = 250 \text{ V}$ and $V_{GS} = -15 \text{ V}$ $V_{DS} = 240 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (nominal 2.92 MeV/nucleon at Brookhaven National Lab Accelerator)	
	2N7472U2, U2L, U2S		Surface LET = 84 MeV-cm ² /mg $\pm 5\%$, range = 28 μm $\pm 7.5\%$, energy = 350 MeV $\pm 7.5\%$ In-situ bias conditions: $V_{DS} = 130 \text{ V}$ and $V_{GS} = 0 \text{ V}$ $V_{DS} = 120 \text{ V}$ and $V_{GS} = -5 \text{ V}$ $V_{DS} = 30 \text{ V}$ and $V_{GS} = -10 \text{ V}$ (typical 1.89 MeV/nucleon at Texas A & M Cyclotron)	

See footnotes at end of table.

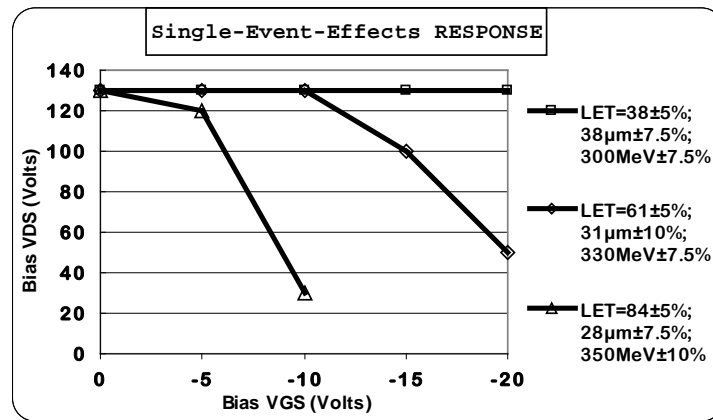
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TABLE V. Manufacturers characterization conditions - Continued.

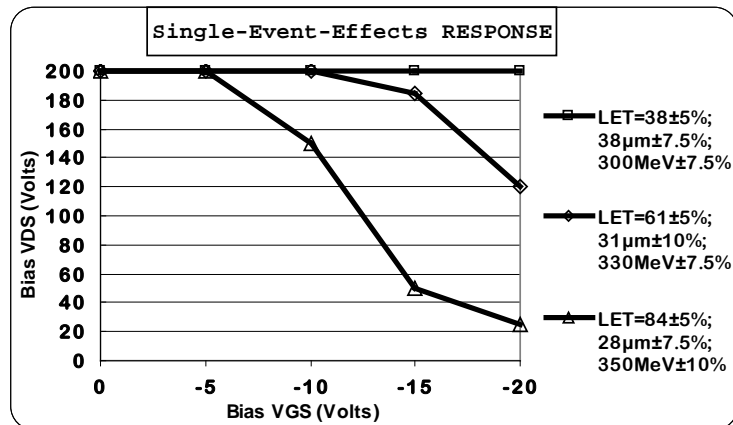
Manufactures cage	Inspection	MIL-STD-750		Sample plan
		Method	Conditions	
	SEE - continued 2N7473U2, U2L, U2S 2N7474U2, U2L, U2S Electrical measurements		<p>In-situ bias conditions: $V_{DS} = 200\text{ V}$ and $V_{GS} = -5\text{ V}$ $V_{DS} = 150\text{ V}$ and $V_{GS} = -10\text{ V}$ $V_{DS} = 50\text{ V}$ and $V_{GS} = -15\text{ V}$ $V_{DS} = 25\text{ V}$ and $V_{GS} = -20\text{ V}$ (nominal 1.98 MeV/nucleon at Brookhaven National Lab Accelerator)</p> <p>In-situ bias conditions: $V_{DS} = 250\text{ V}$ and $V_{GS} = -5\text{ V}$ $V_{DS} = 225\text{ V}$ and $V_{GS} = -10\text{ V}$ $V_{DS} = 175\text{ V}$ and $V_{GS} = -15\text{ V}$ $V_{DS} = 50\text{ V}$ and $V_{GS} = -20\text{ V}$ (nominal 1.98 MeV/nucleon at Brookhaven National Lab Accelerator)</p> <p>I_{GSSF1}, I_{GSSR1}, and I_{DSS1} in accordance with table I, subgroup 2</p>	
<div>Upon qualification, all manufacturers should provide the verification test conditions to be added to this table.</div>				

1/ I_{GSSF1} , I_{GSSR1} , and I_{DSS1} was examined before and following SEE irradiation to determine acceptability for each bias condition. Other test conditions in accordance with [table I](#), subgroup 2, may be performed at the manufacturer's option.

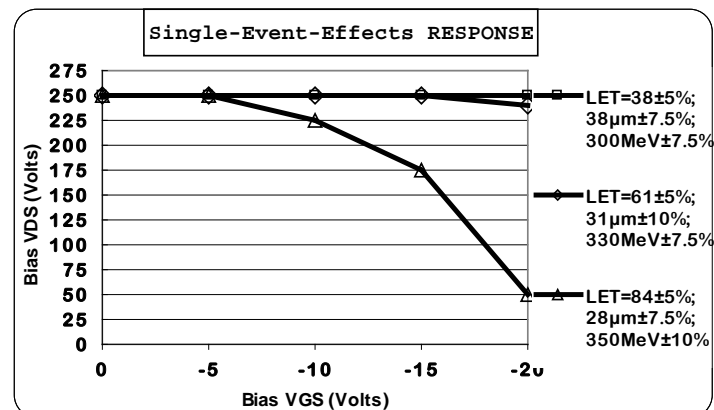
2N7472U2, U2L, U2S



2N7473U2, U2L, U2S



2N7474U2, U2L, U2S



*

FIGURE 9. Cage 68210 typical SEE response graph.

6.9 Request for new types and configurations. Requests for new device types or configurations for inclusions in this specification sheet should be submitted to: DLA Land and Maritime, ATTN: VAC, Post Office Box 3990, Columbus, OH 43218–3990 or by electronic mail at Semiconductor@dla.mil or by facsimile (614) 693-1642 or DSN 850-6939.

6.10 Changes from previous issue. The margins of this specification are marked with asterisks to indicate where changes from the previous issue were made. This was done as a convenience only and the Government assumes no liability whatsoever for any inaccuracies in these notations. Bidders and contractors are cautioned to evaluate the requirements of this document based on the entire content irrespective of the marginal notations and relationship to the last previous issue.

Custodians:
Army - CR
Navy - EC
Air Force - 85
NASA - NA
DLA - CC

Preparing activity:
DLA - CC

(Project 5961-2016-068)

Review activity:
Air Force - 99

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